

Epic TechWatch 2023

@ W3+ Fair Jena 30.11.2023



„Innovations in Ion Beam Machining“

Dr. Christian Schindler

Close to customers

Global network


Family owned


Innovation and education

 12,700
FTE employees

 140
Countries

 CHF 3.0 bn
Turnover

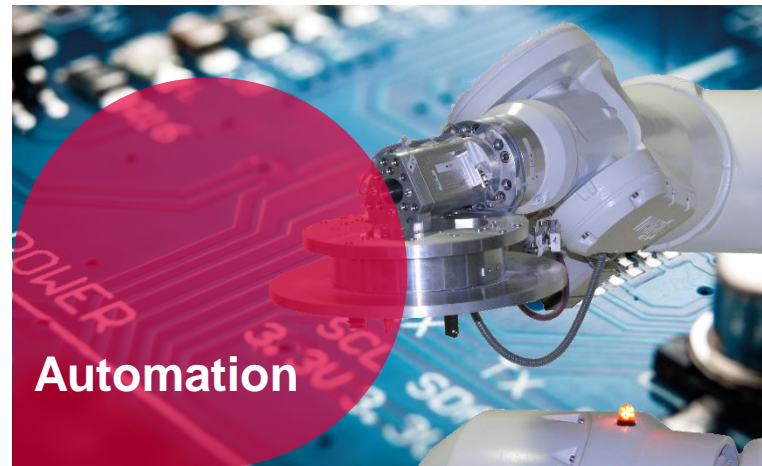
 5%
of turnover for innovation

 49.8%
Equity ratio

Buhler Product Line

Center of Competence Leipzig

Correcting,
Structuring and
Smoothing of
Surfaces



Substrate
Handling,
Automation

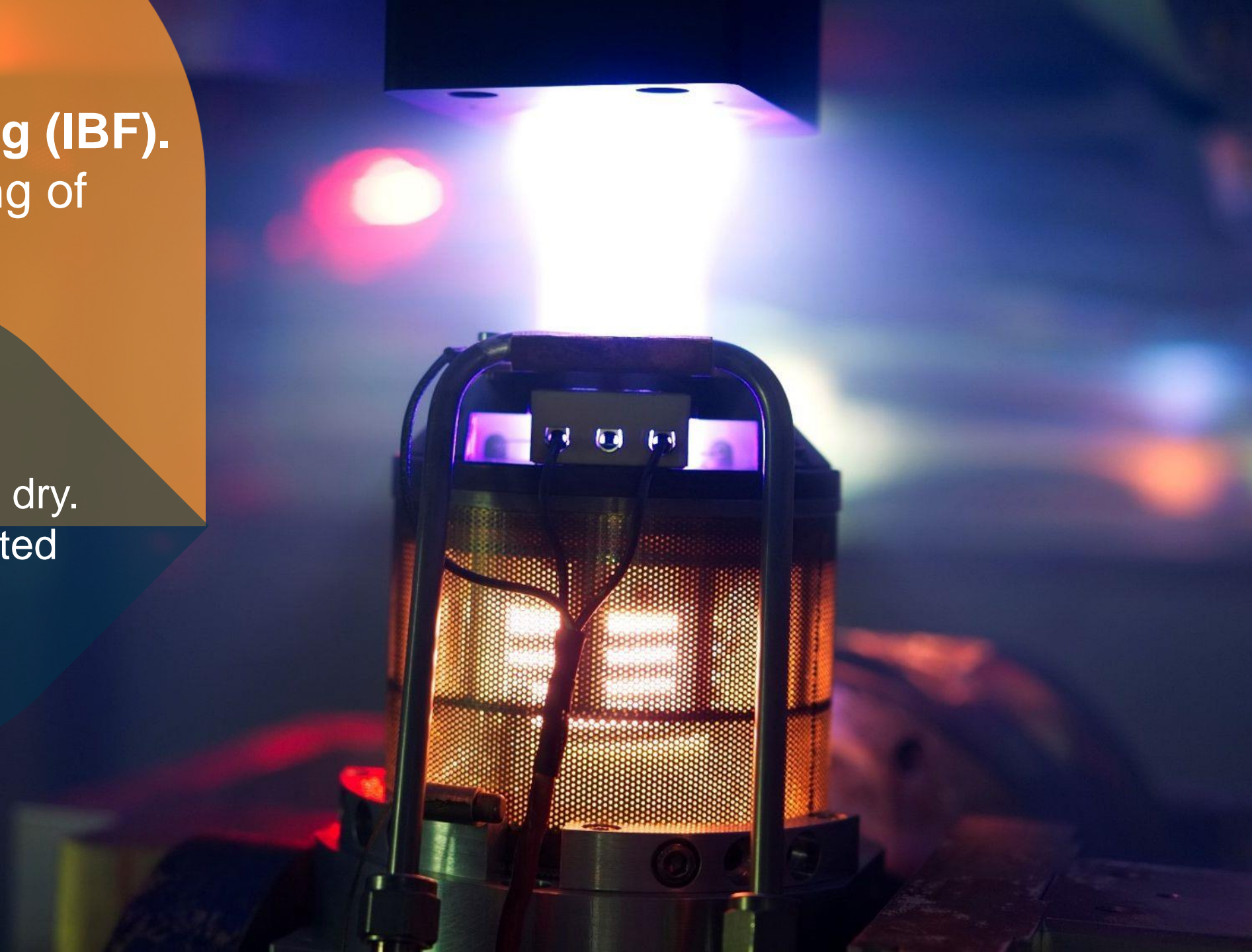
Coating
Thickness
Control



Thin Film and
Thickness
Measurement
etc.

Ion Beam Figuring (IBF).
Corrective polishing of
surfaces.

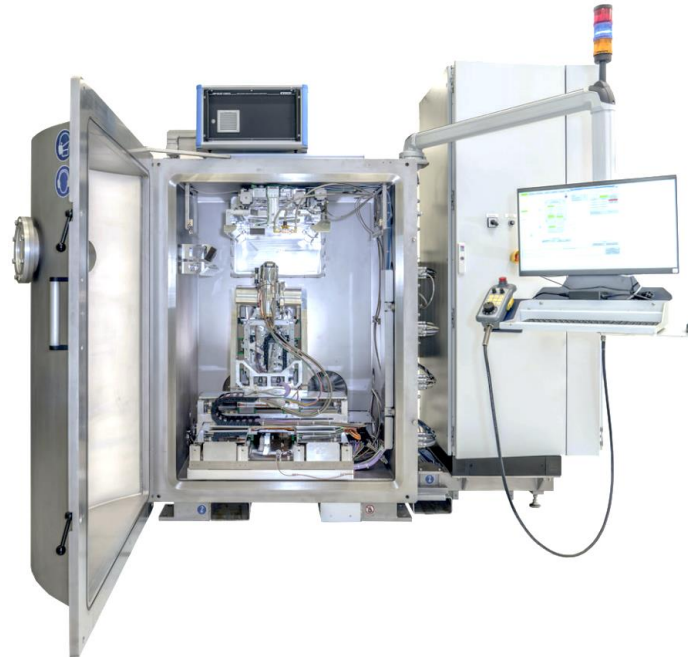
Contactless and dry.
Using accelerated
argon ions.



Center of Competence Leipzig

Production Equipment for Correcting, Structuring and Smoothing of Surfaces

For precise figure correction and smoothing of high-end optics



Leybold Optics IBF - Series

For precise flattening and correction of features on a wafer

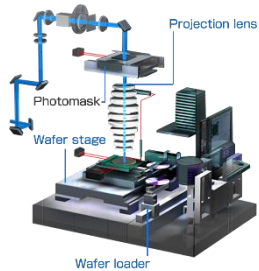


Leybold Optics IBT800

Applications of Ion Beam Figuring (IBF)

Ultraprecision as standard

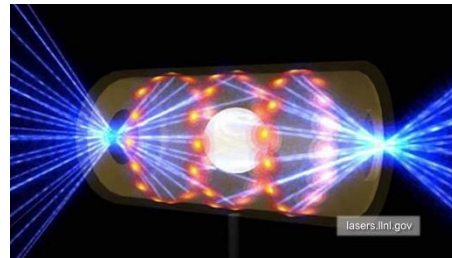
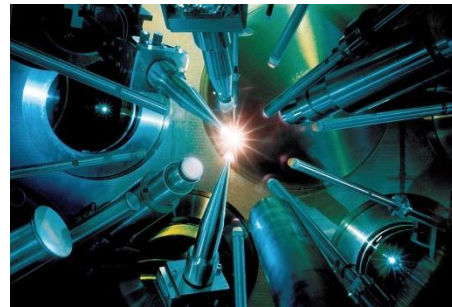
Lithography
Optics.



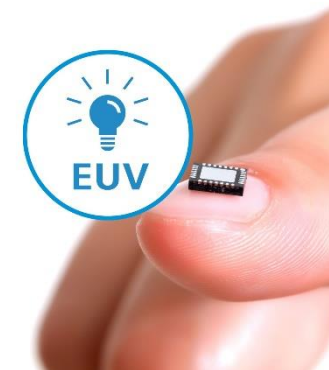
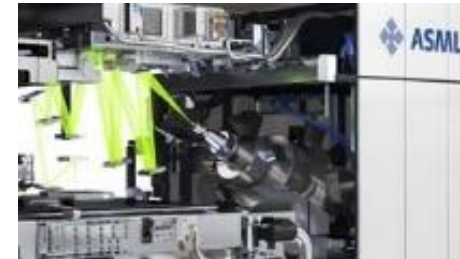
Optics for
Telescopes.



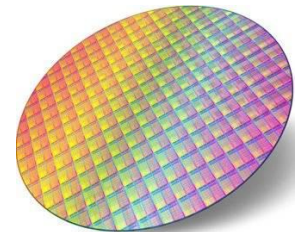
Laser Optics.



Deep and
Extreme UV



Wafer-holder
& Stepper
chucks

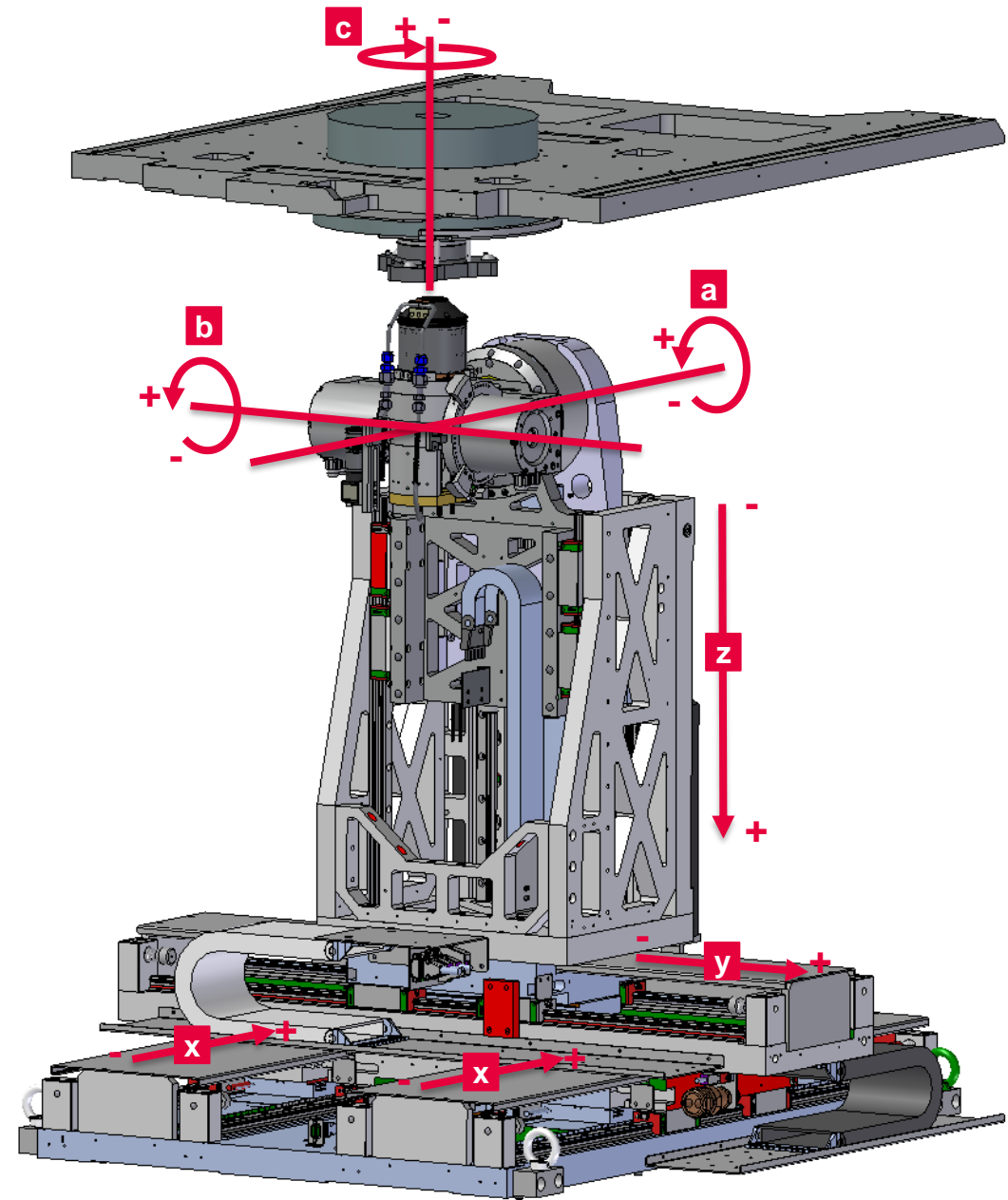
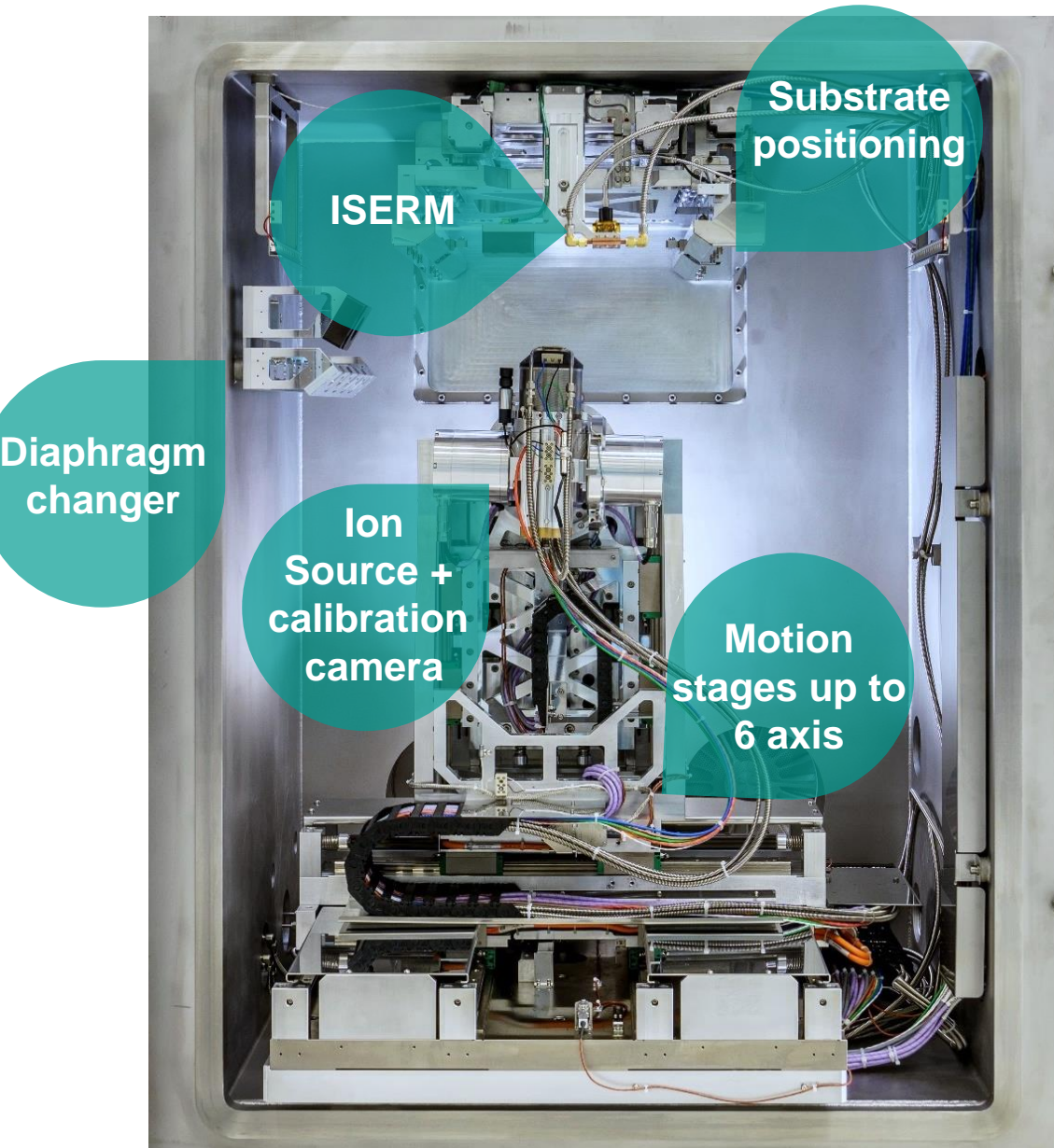




Leybold Optics IBF. Machine Portfolio (Number of Axes: 3, 5 or 6).

Model	IBF 200	IBF 450	IBF 600	IBF 800	IBF 1200	IBF 1500	IBF 2100
Max. diameter of flat samples	200 mm	500 mm	600 mm	800 mm	1200 mm	1500 mm	2100 mm
Max. weight	35 kg	100 kg	100 kg	100 kg	300 kg	1000 kg	1500 kg

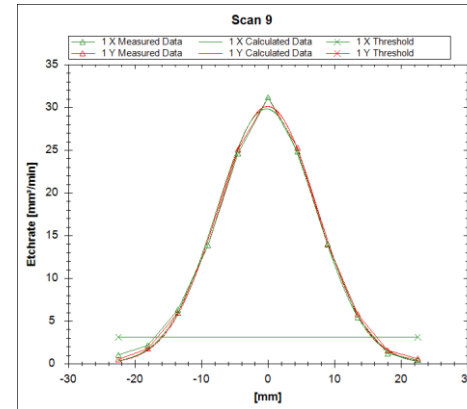
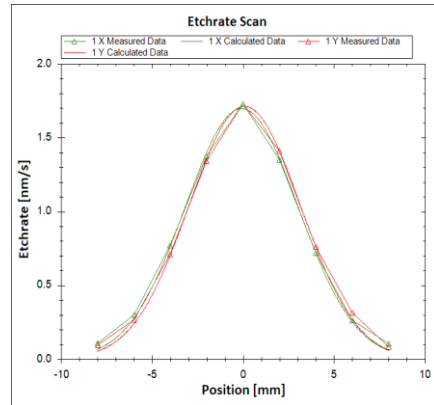
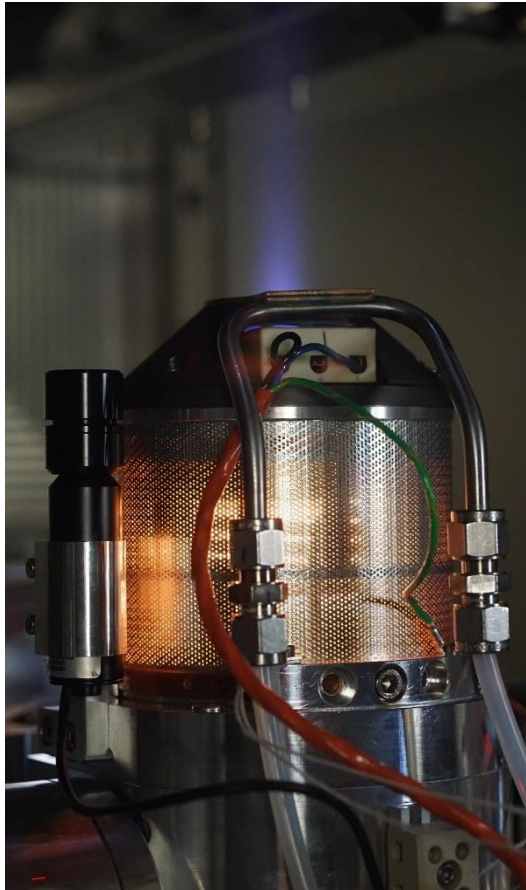
Leybold Optics IBF Inside View.



Leybold Optics IBF

Reproducible and Longterm Stable IB-Sources for Material Removal

RF40 ion beam source



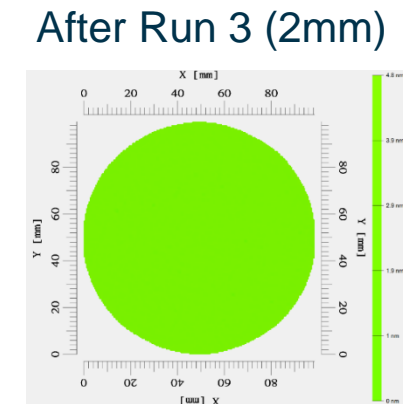
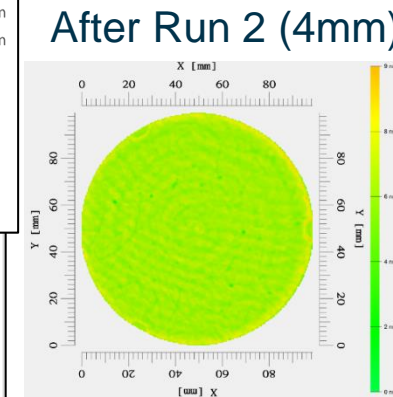
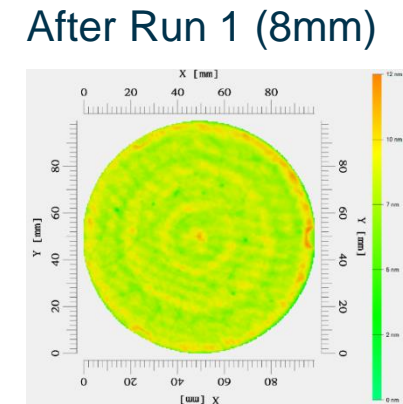
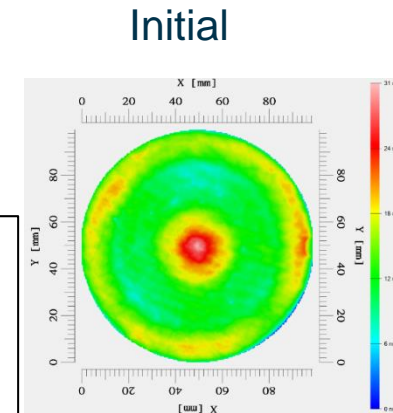
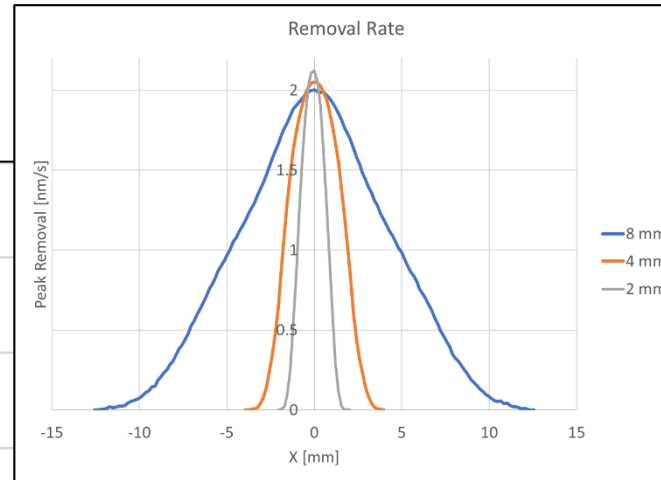
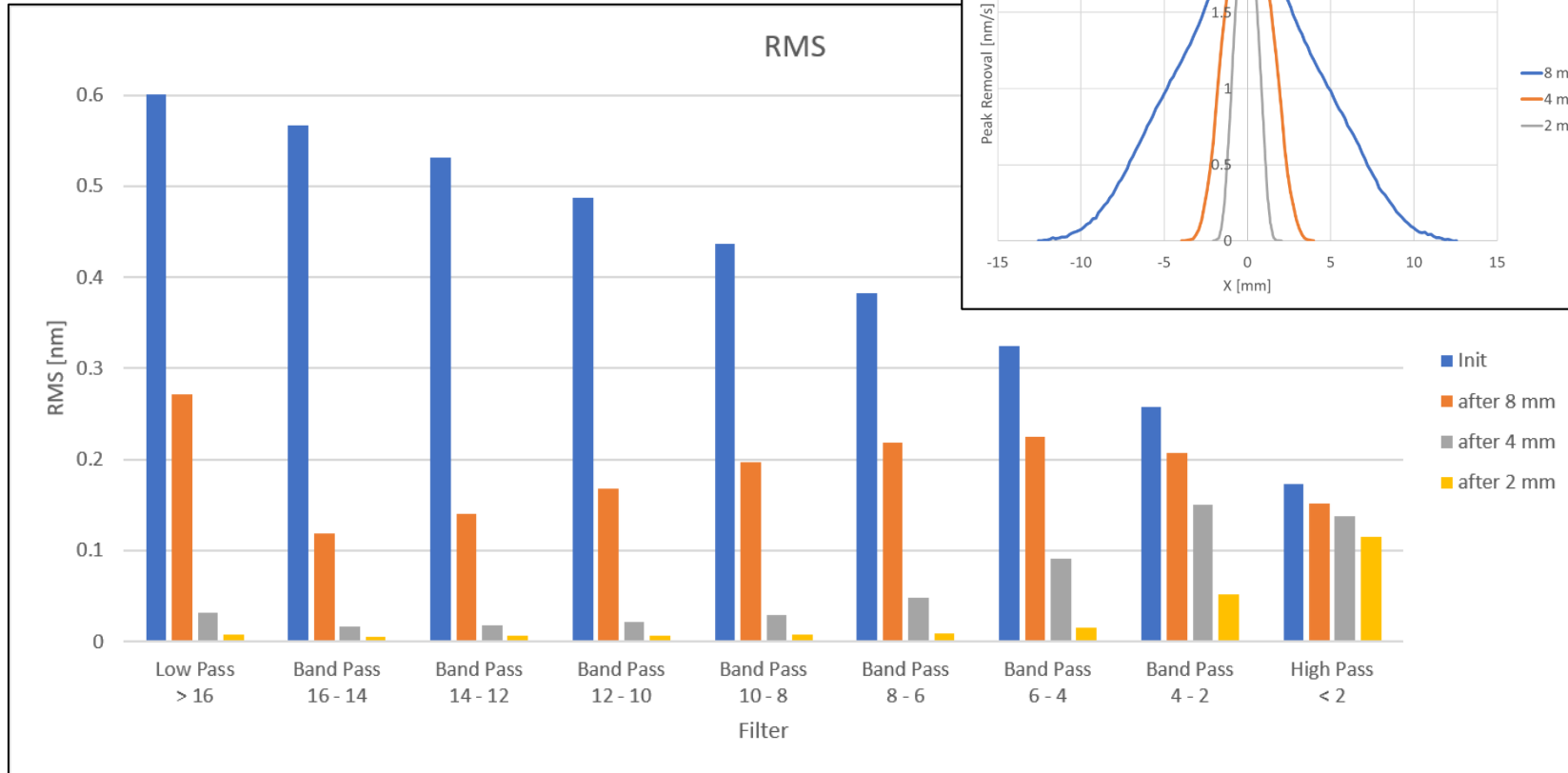
Representative ISERM-Scans and Source Parameter

1,8 nm/s	Peak Etch Rate	30 nm/s
9 mm	Spot Size (FWHM)	17.5 mm
0,01mm ³ /min	Removal Rate	0.63 mm ³ /min

RF80 ion beam source



Iterative Processing



Etch rate measurement

Initial situation

- Every ion beam source has its own characteristic and working point
- Individual beam center and etch rate needs to be determined

Standard measurement is done via 2 steps

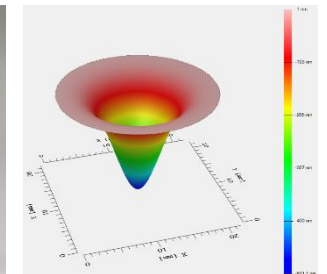
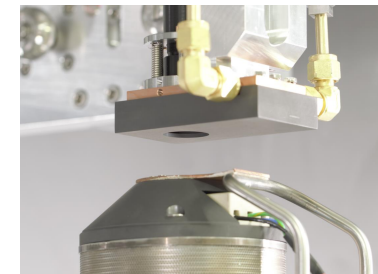
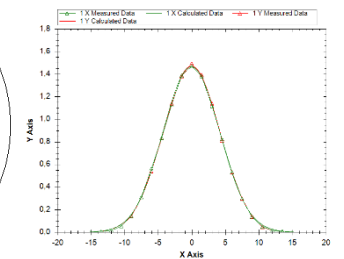
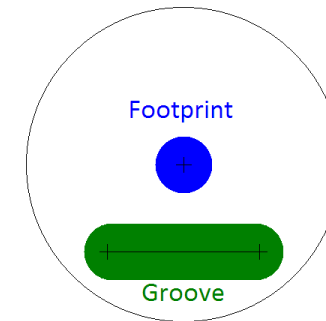
1. Measure beam current over beam profile with faraday cup and extract a graph to obtain gaussian shape and beam center (only indirect, uncertain etch rate determination)
 2. Perform a footprint or groove etching on sample to analyse etch rate outside of machine
- High effort to obtain actual etch rate and monitor longterm degeneration of source (drift sums up to ~10% after 500h)

ISERM

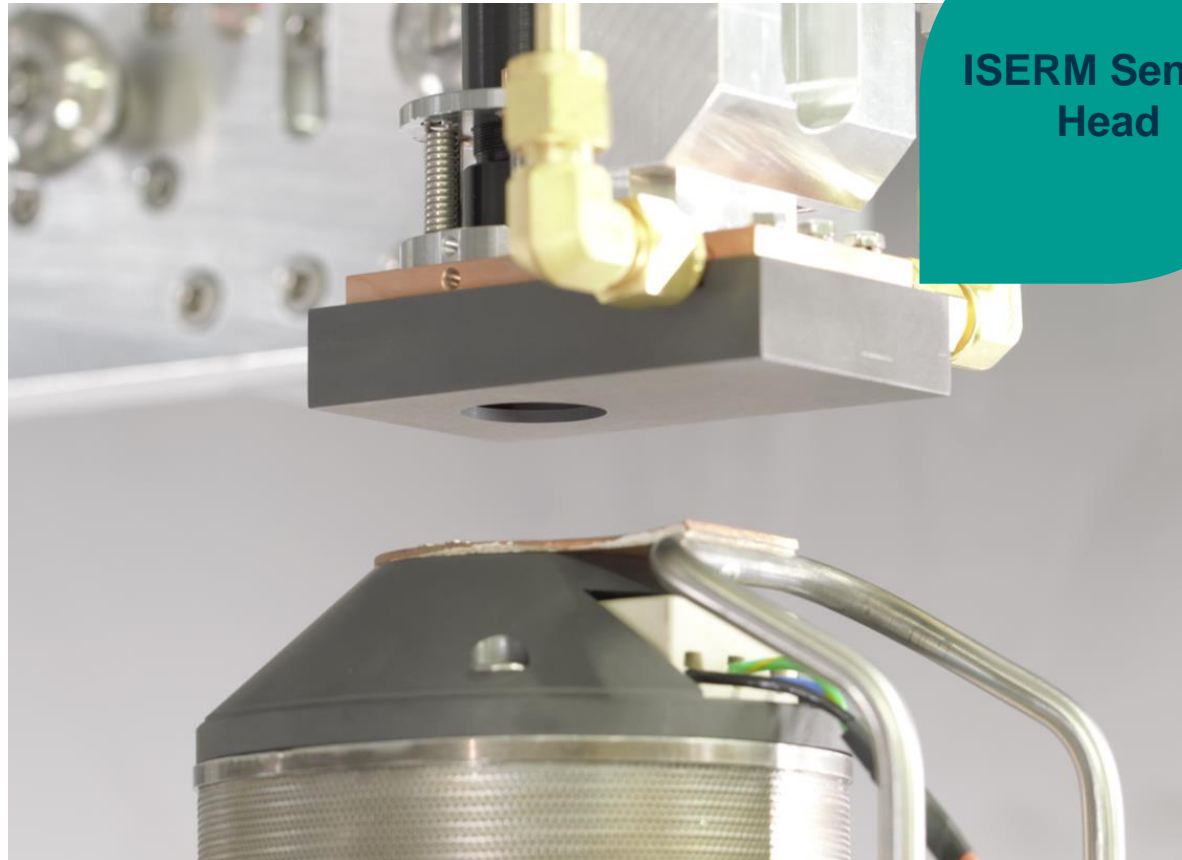
- Direct determine etch rate with actual beam parameter and material in the machine
- Enable regular process calibration and secure production yield by stable material removal and predictive maintenance
- Obtain basis for process simulation



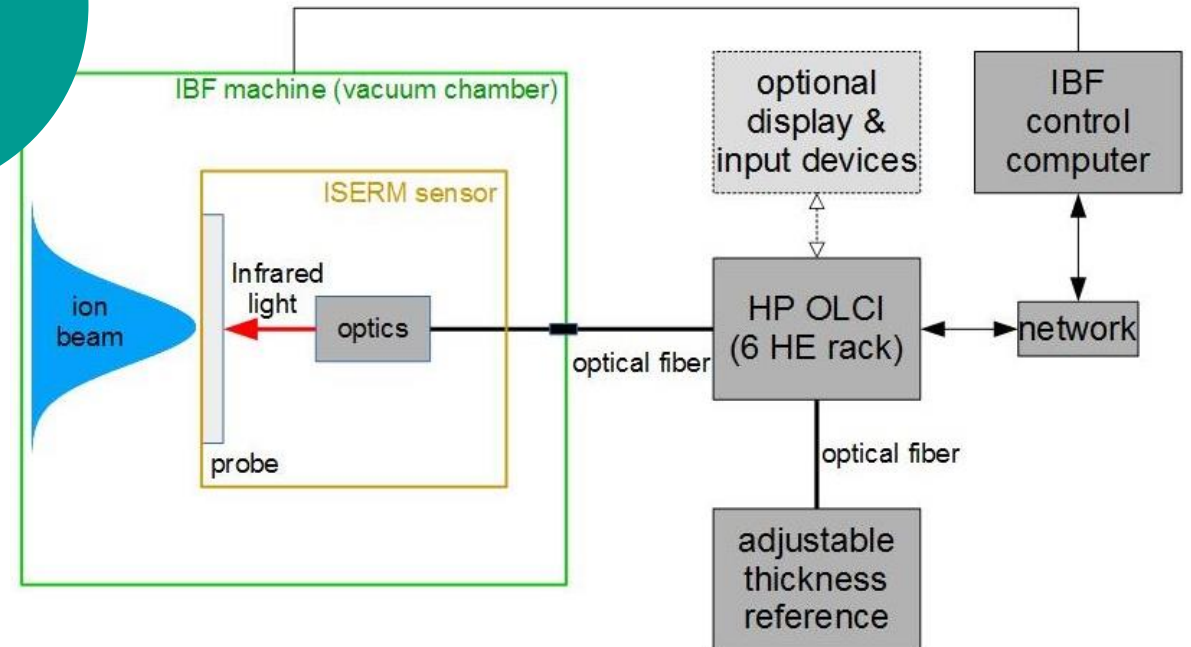
RF power: < 300 W
Ion energy: < 1500 eV
Ion current: < 150 mA
Accelerator voltage: < 1000 V



In-Situ Etch Rate Measurement System - ISERM



ISERM Sensor Head



Automation Solutions for IBF

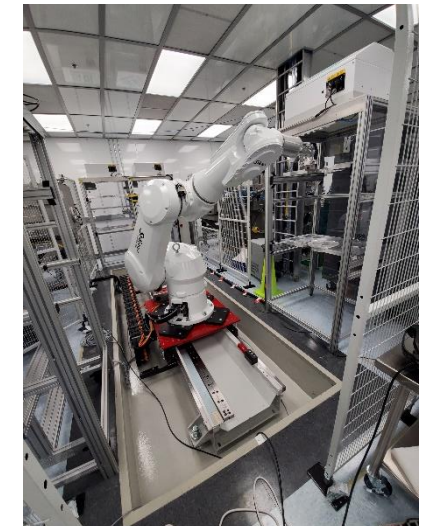
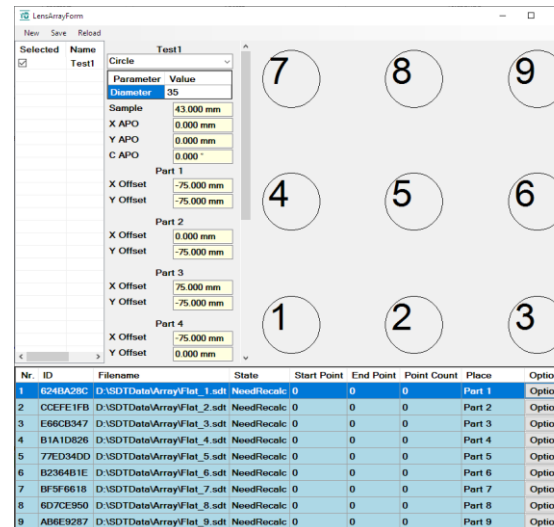
Robotic handling

- Combined loading of several IBF machines within robotic cell on rails
- work stocker arrangement
- 24/7 operation mode
- Flexible actuator design



Array machining

- Take advantage of larger equipment for small samples to increase efficiency
- Full software support for metrology and operations
- Quick setup and low offset time



Innovations for a
better world.

